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PAIRABE	U.S. DEPARTMENT	OF COMMERCE	
	PATENT AND TRAD	EMARK OFFICE	
SUPPLEMENTAL	LINFORMATION	Docket Number:	
DISCLOSURE STATEMENT		52433/861	
Application Number:	Filing Date:	Examiner:	Art Unit:
10/591,093	August 29, 2006	Not Yet Assigned	Not Yet Assigned
Title:		Applicant(s):	
METHOD FOR REMOVING BORON FROM SILICON		Jiro KONDO, et al.	

Address to:

Mail Stop Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450 I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to:

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Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450

COR

Alypa Sullivar

Sir:

- 1. In accordance with the duty of disclosure under 37 C.F.R. § 1.56 and in conformance with the procedures of 37 C.F.R. § 1.97 and 1.98 and M.P.E.P. § 609, attorney(s) for Applicant(s) hereby bring the reference(s) listed on the attached modified PTO Form No. 1449 to the attention of the Examiner. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom.
- 2. A copy of each patent, publication or other information listed on the modified PTO form 1449 is enclosed, except as otherwise indicated.
- 3. It is believed that no fees are due in connection with this Supplemental Information Disclosure Statement. However, should any fees be due, the Commissioner is authorized to charge Deposit Account No. 11-0600 for such fees. A duplicate copy of this communication is enclosed for charging purposes.

Respectfully submitted,

Dated: October 18, 2006

By: John J. Kelly, X John J. Kelly, Jr. (Reg. No. 29,182)

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CUSTOMER NO. 26646



DOCKET NO. 52433/861 APPLICANT SERIAL NO. 10/591,093

INFORMATION DISCLOSURE STATEMENT BY APPLICANT PTO-1449 Jiro KONDO, et al.

FILING DATE	GROUP
August 29, 2006	Not Yet Assigned

## U. S. PATENT DOCUMENTS

	EXAMINER INITIAL	PATENT/PUBLICATION NUMBER	PATENT/PUBLICATION DATE	NAME	CLASS	SUBCLASS	FILING DATE	
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/SC/	Mitsuru Tanahashi et al., Distribution Behavior of Boron Between Sio <sub>2</sub> -saturated NaO <sub>2.5</sub> -CaO-Sio <sub>2</sub> Flux and Molten Silicon, Journal of the Mining and Materials, Processing Institute of Japan, Vol. 118, No. 7, Pages 497-505, 2002
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EXAMINER DATE CONSIDERED 07/18/2008 /Stefanie Cohen/

EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.